



# A New Method to Grow SiC: Solvent-Laser Heated Floating Zone

Andrew A. Woodworth, Philip G. Neudeck, and Ali Sayir

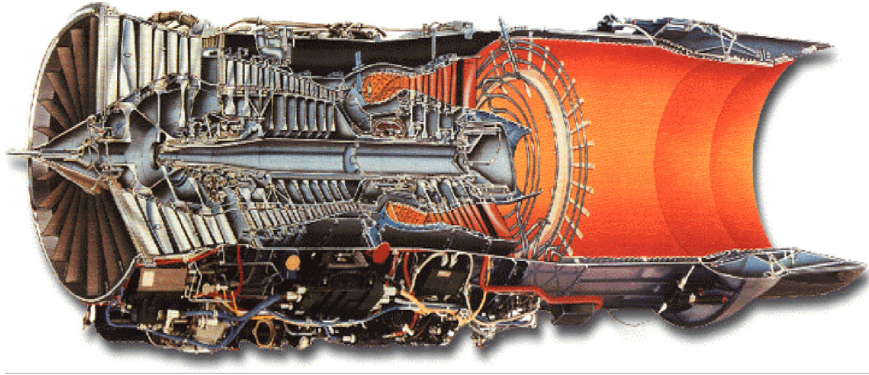


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[www.nasa.gov](http://www.nasa.gov)

# SiC Electronics Benefits to NASA Missions

Intelligent Propulsion Systems



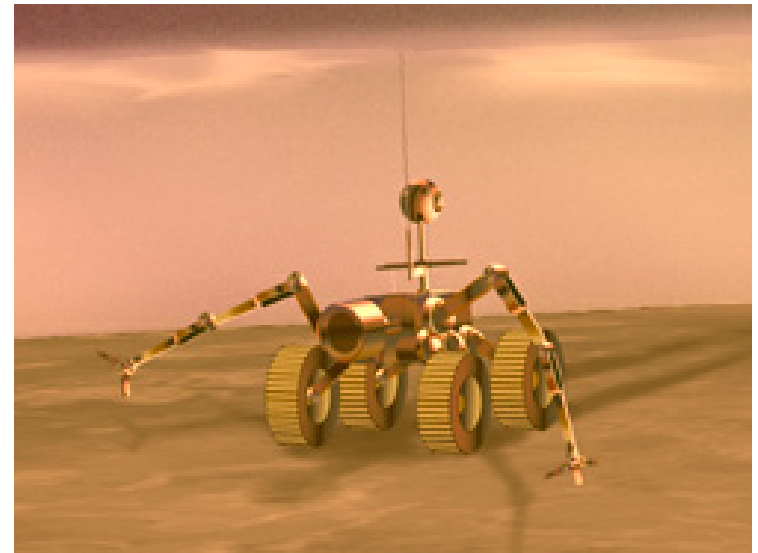
Space Exploration Vision PMAD



More Electric + Distributed Control Aircraft



Venus Exploration

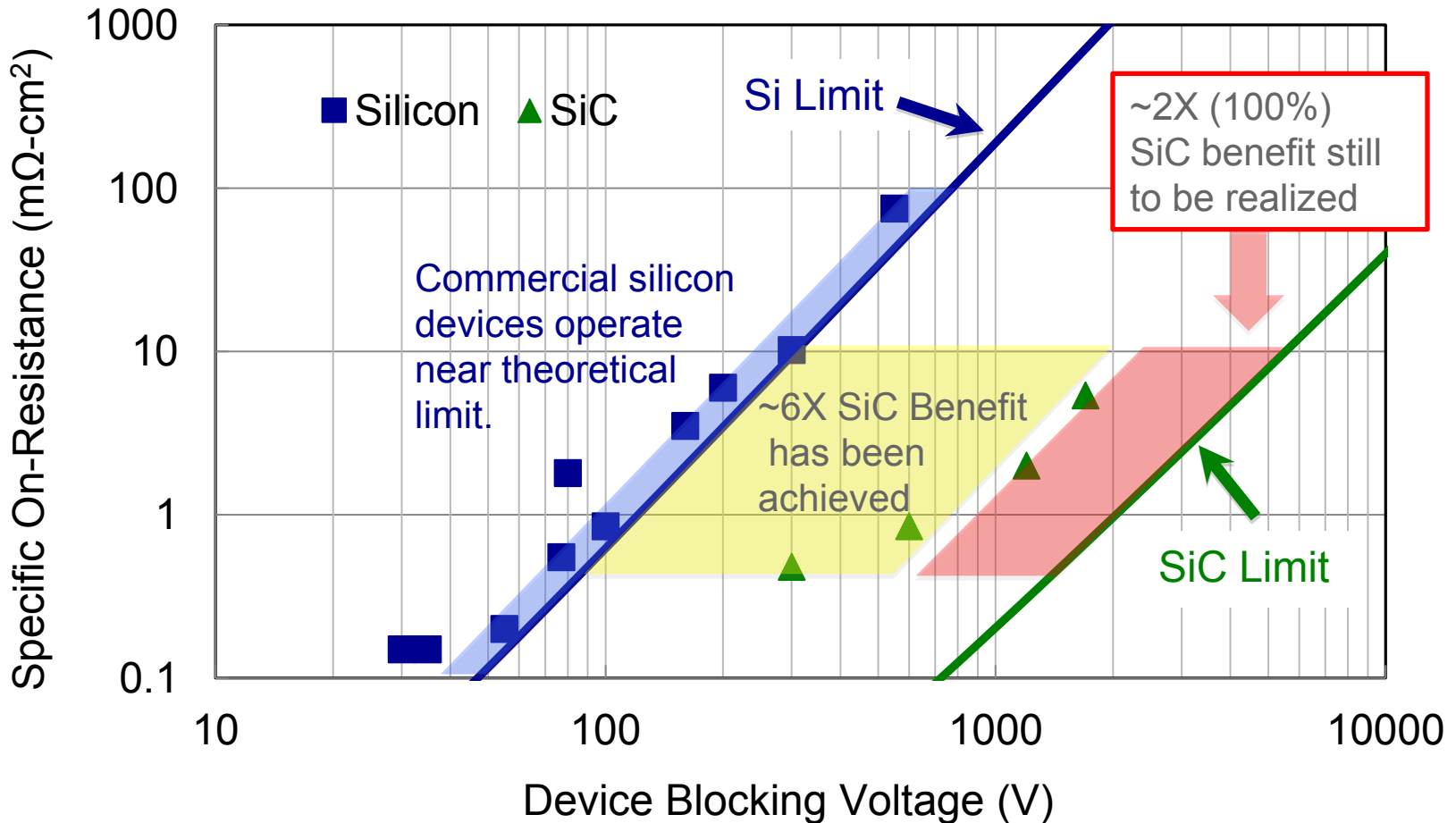


**All combinations of high temperature and/or high power applications!**

# Unipolar Power Device Comparison

(Volume Production Commercial Devices)

SiC devices are ~2X voltage or current-density **de-rated** from theoretical material performance.

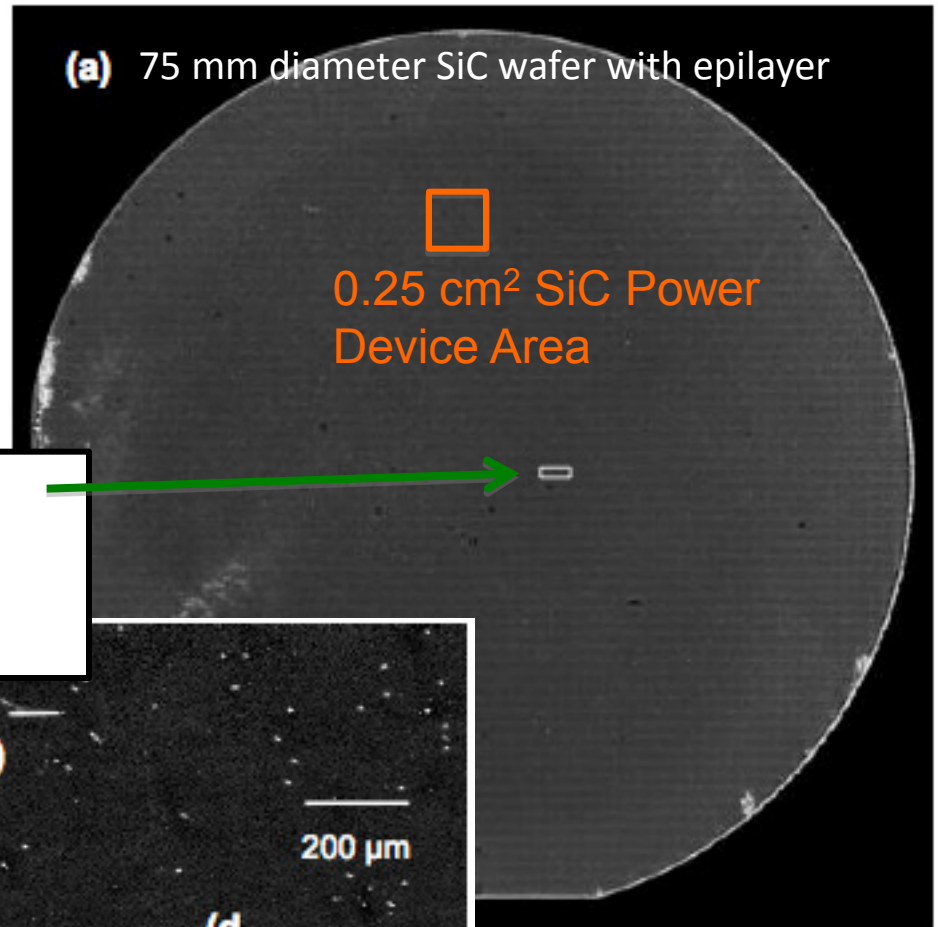


Above comparison does NOT take yield, cost, other relevant metrics into account.



# SiC Wafer Material Defects

Over the past decade there have been numerous studies (including NASA GRC) linking degraded SiC power device performance, yield, and reliability to the presence of defects in the SiC wafer crystal.



Magnified view small area in middle of wafer imaged by Ultra-Violet Photoluminescence

- Each white dot or line is a dislocation defect!
- Average dislocation density  $\sim 10^4$  per cm<sup>2</sup>

Stahlbush et. al., Mat. Sci. Forum vol. 556 p. 295 (2007)

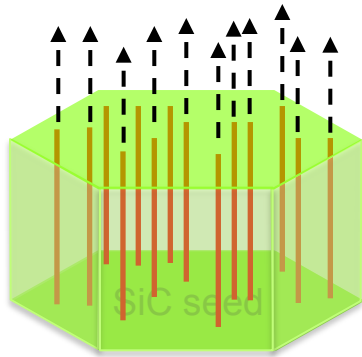
Two-fold defect-induced SiC device over-design roughly translates into corresponding energy loss and/or power circuit size increase trade-off.

# Description of Technology/Approach

Large Tapered Crystal (LTC) SiC Growth

## Present SiC Growth Process

(Vapor transport)



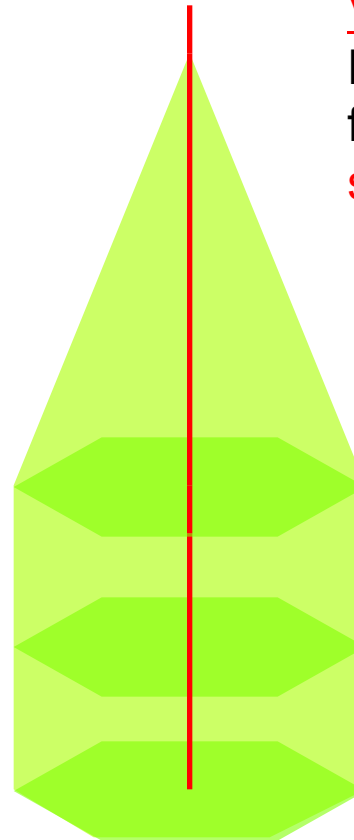
Vertical (c-axis) growth proceeds from top surface of large-area seed **via thousands of screw dislocations.** (i.e., **dislocation-mediated growth!**)

Crystal grown at  $T > 2200^{\circ} \text{C}$   
High thermal gradient & stress.

Limited crystal thickness.

## Proposed LTC Growth Process

(US Patent 7,449,065 OAI, Sest, NASA)



### Vertical Growth Process:

Elongate small-diameter fiber seed grown from **single SiC dislocation.**

### Lateral Growth Process:

CVD grow to enlarge fiber sidewalls into large boule.

- $1600^{\circ} \text{C}$ , lower stress
- Only 1 dislocation

**Lateral** & **vertical** growth are simultaneous & continuous (creates tapered shape).

Radically change the SiC growth process geometry to enable full SiC benefit to power systems.

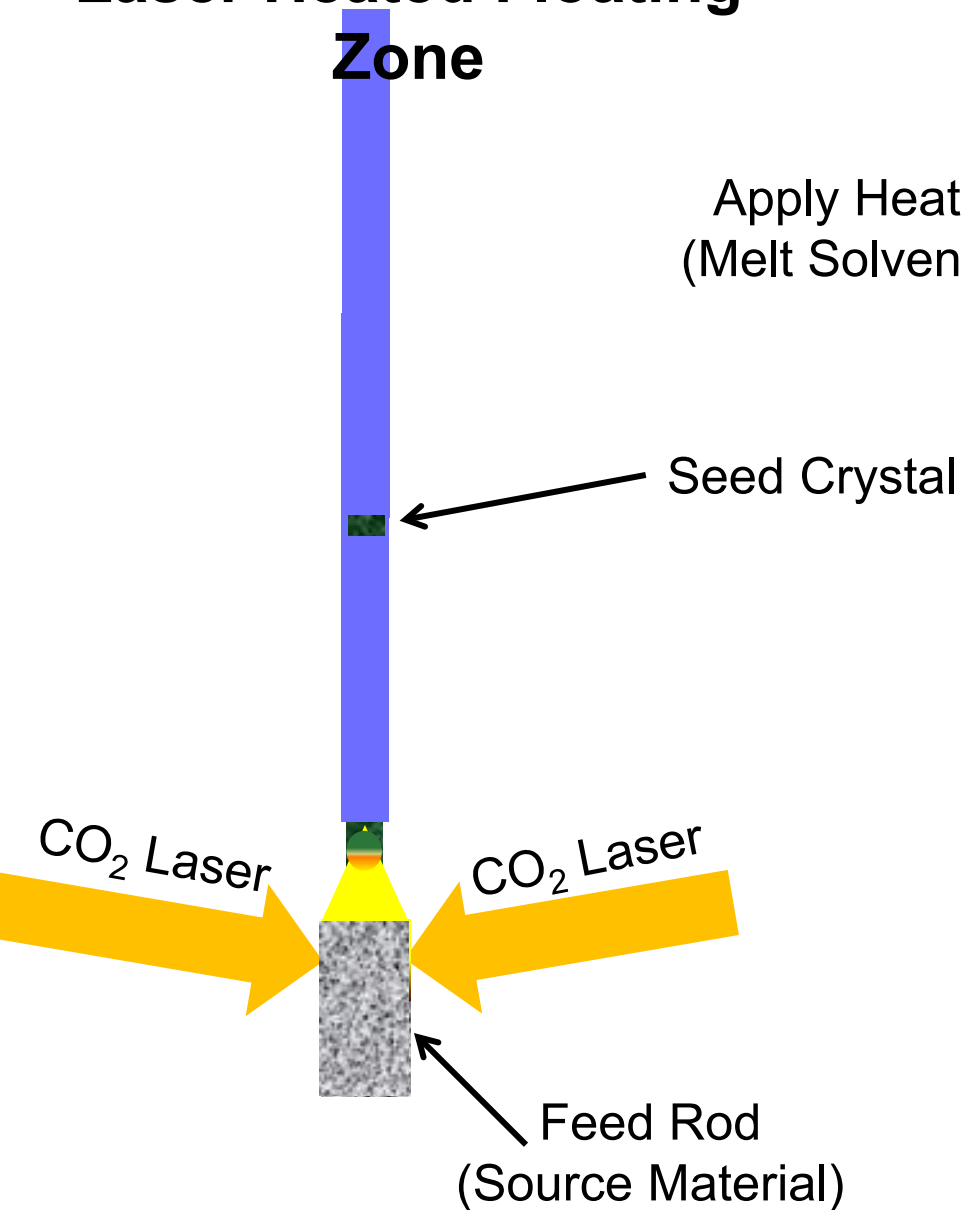
# Solvent-LHFZ Technique

Laser Heated Floating

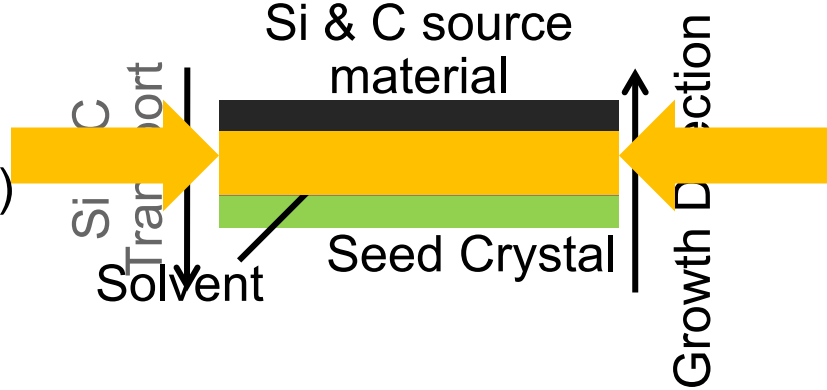
+

Solvent Growth Method

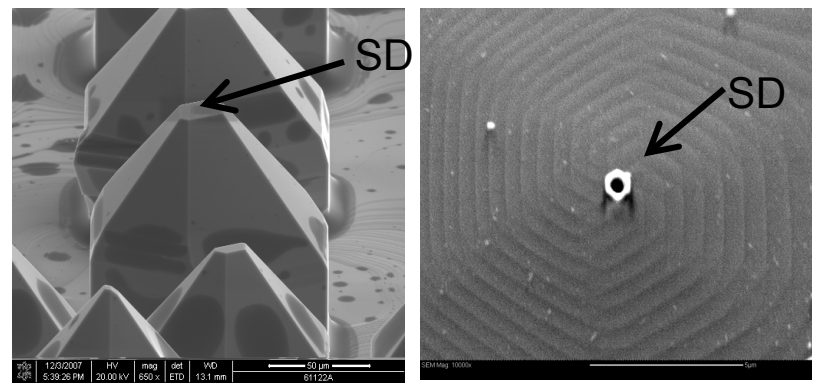
Zone



Apply Heat (Melt Solvent)

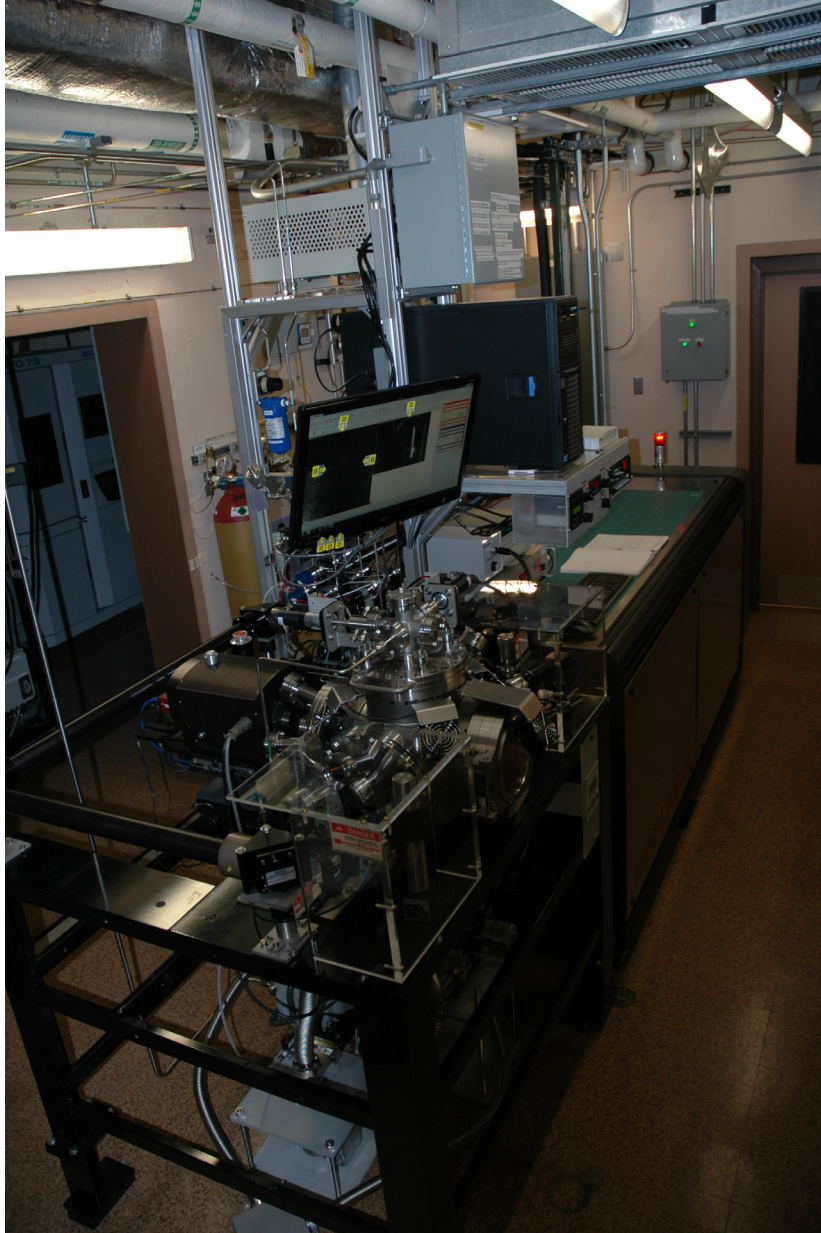


## Seed Crystal



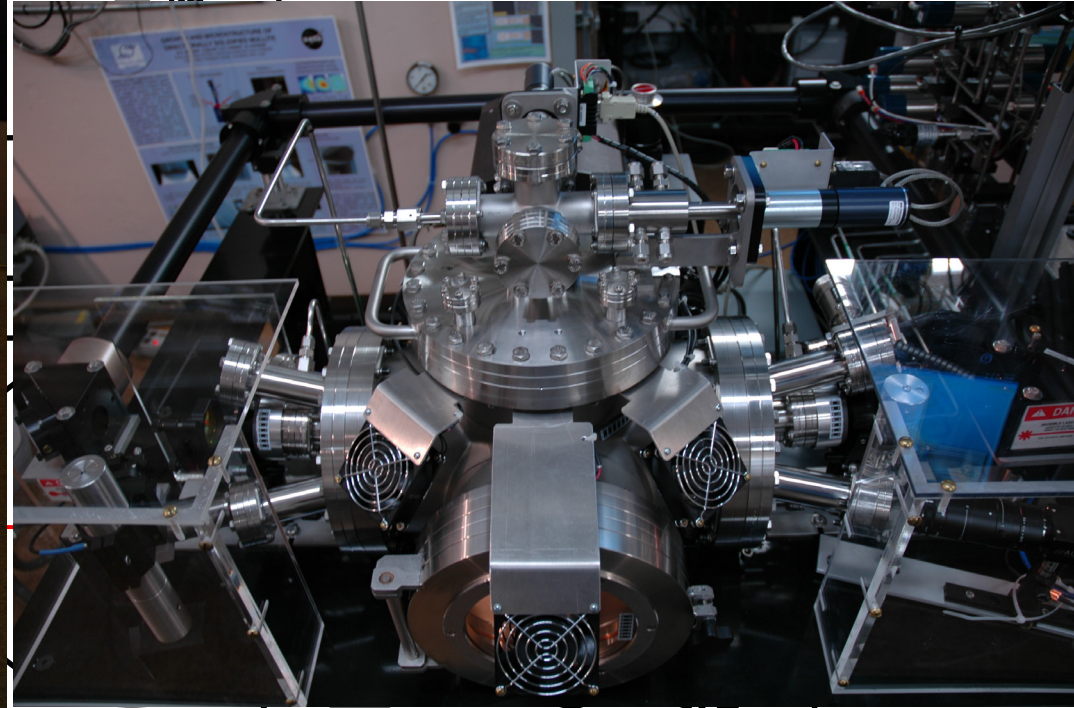


# The Solvent-LHFZ System

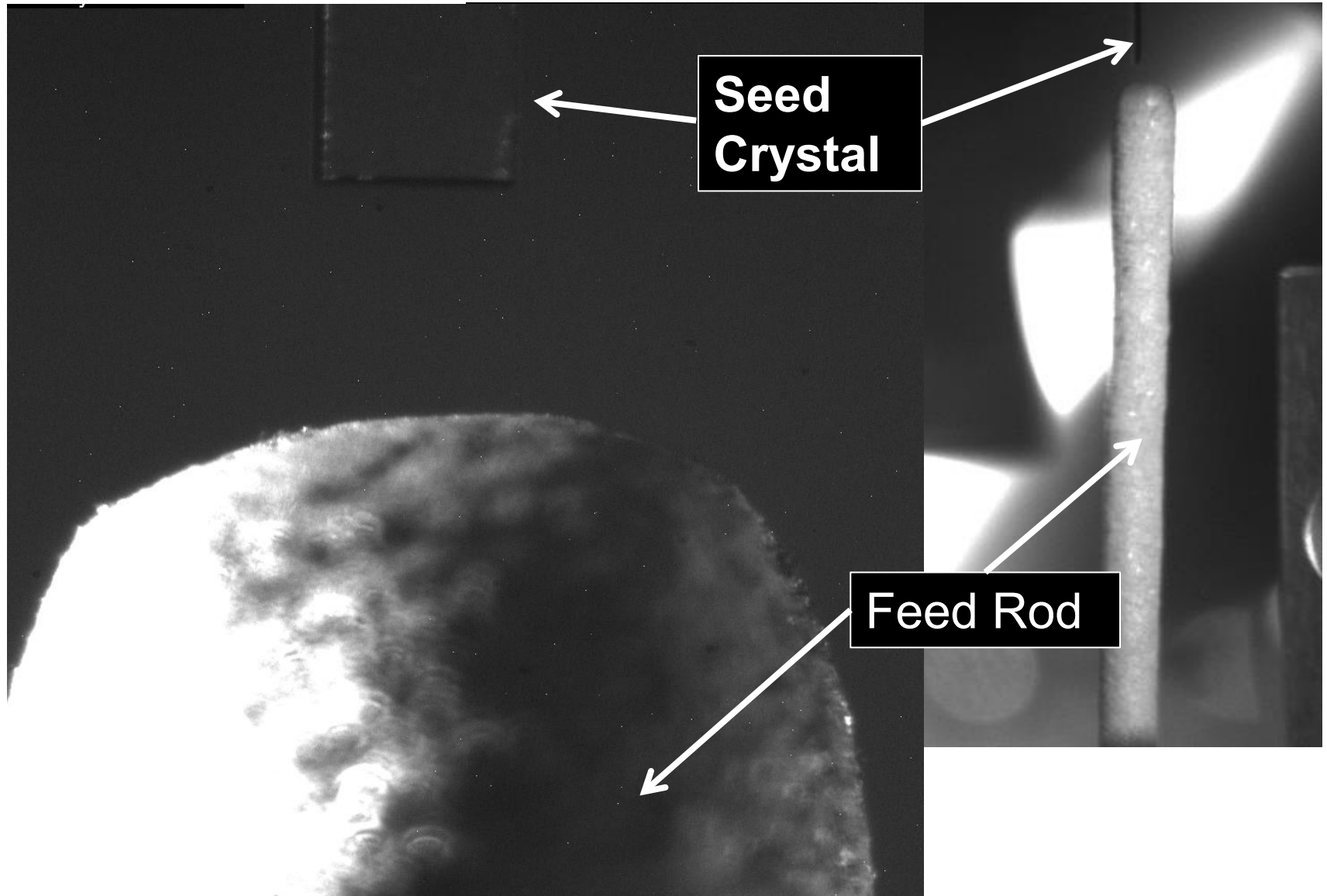


long range  
optical  
microscope

**Top Down View**



# Growth Mechanics

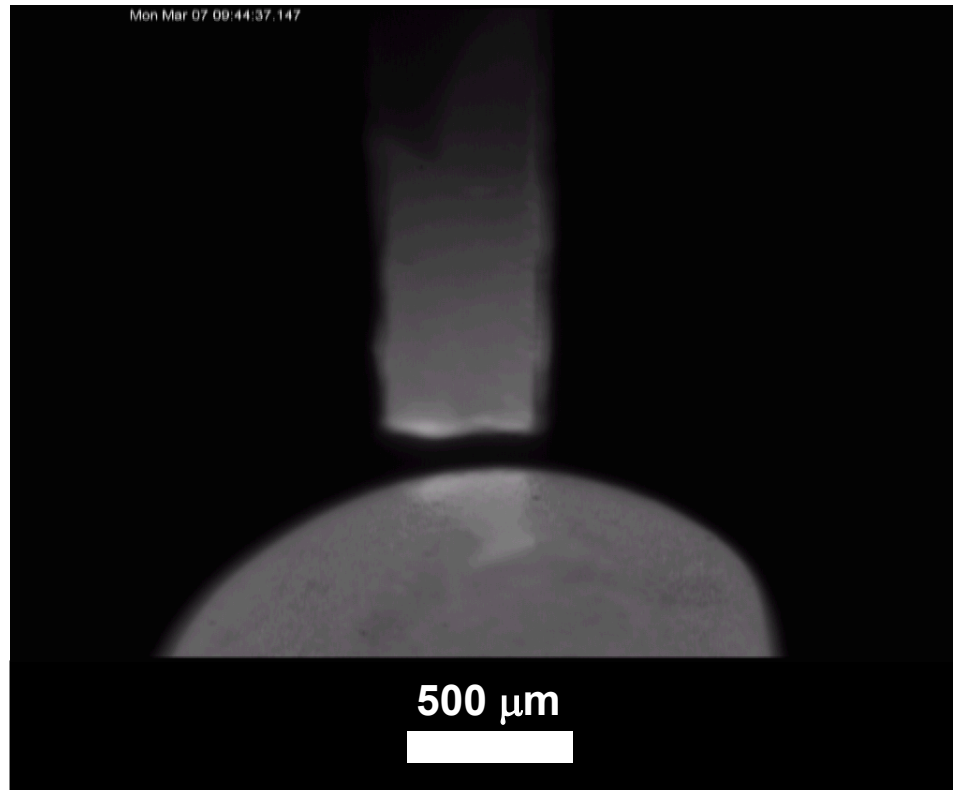


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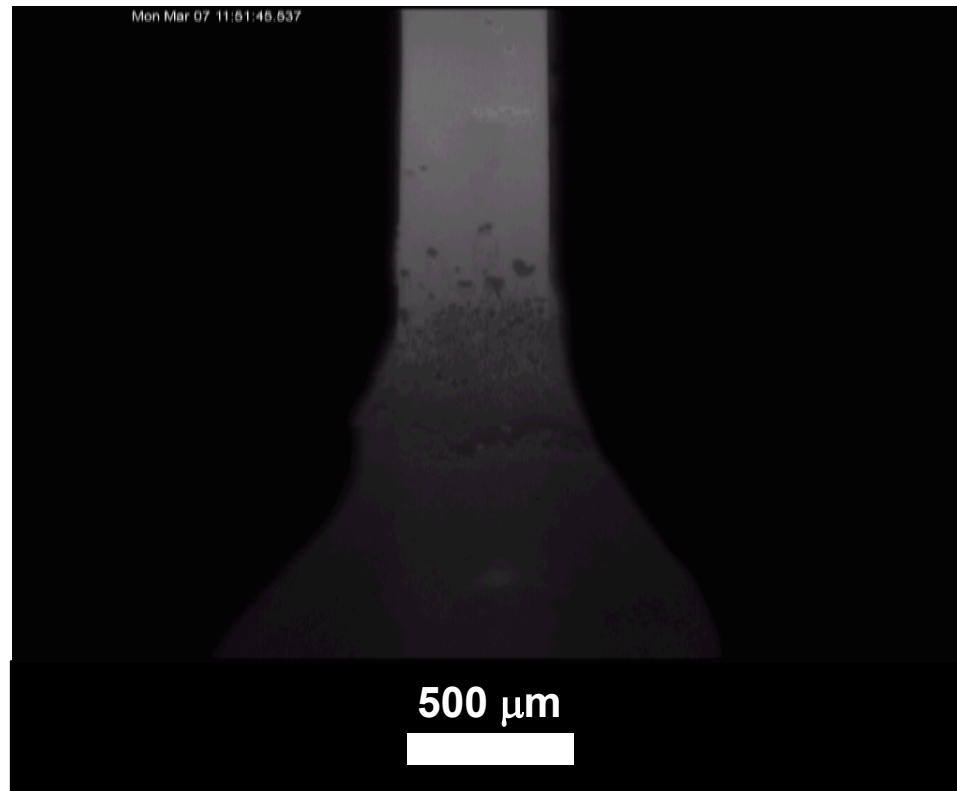
# Growth Mechanics

## Contact and Wetting

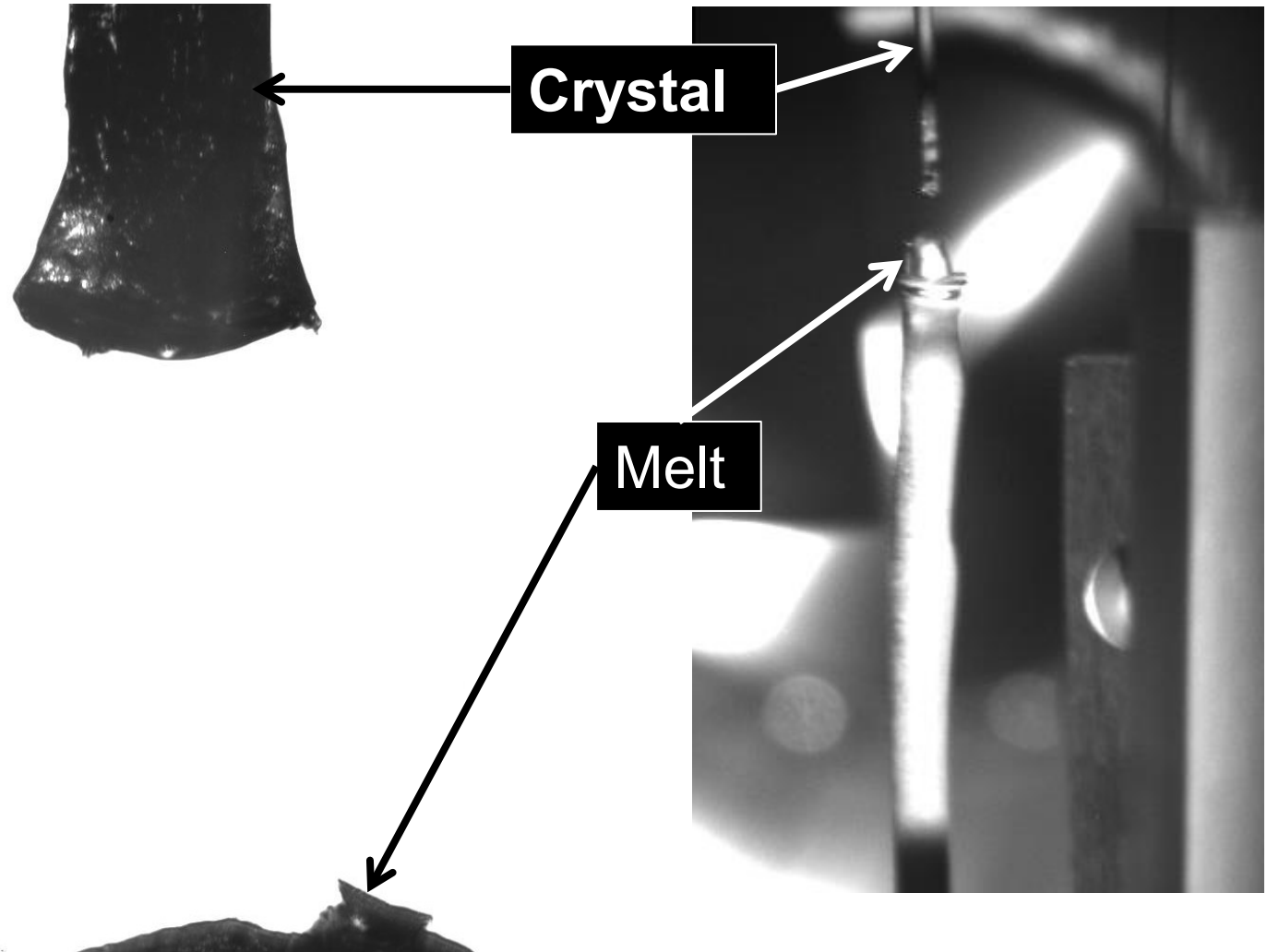


# Growth Mechanics

## End of Growth Experiment



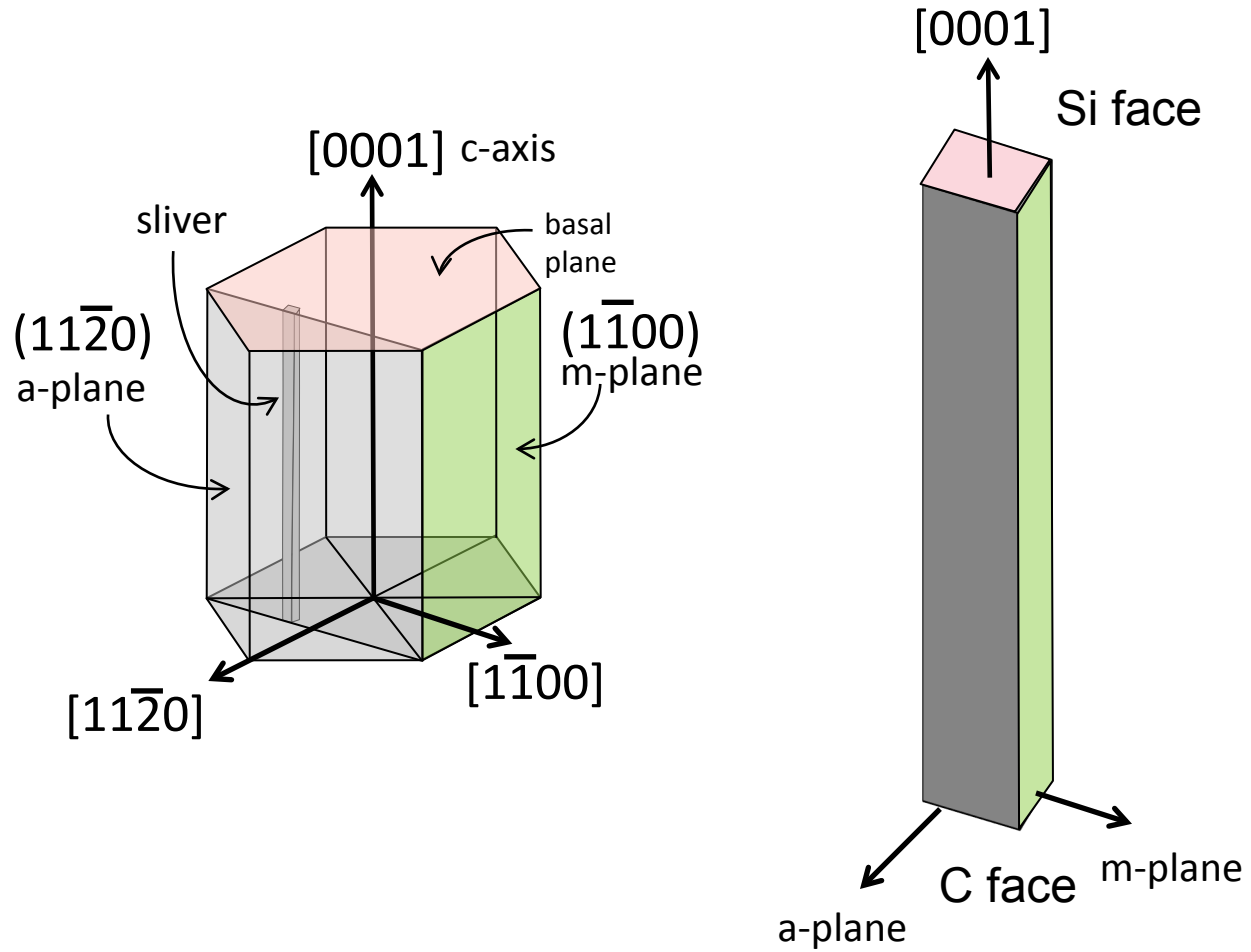
# Growth Mechanics-After



After growth the crystal is put into HF:HNO<sub>3</sub>:HCl (1:1:2) bath to remove extra source material

# Seed Crystals

## 4H-SiC





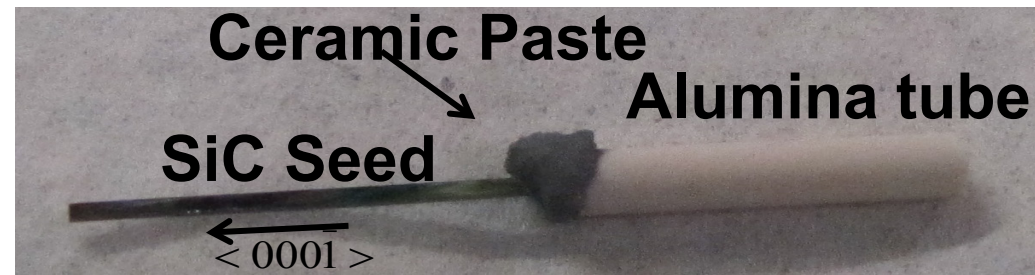
# Seed Crystals

## Growth face

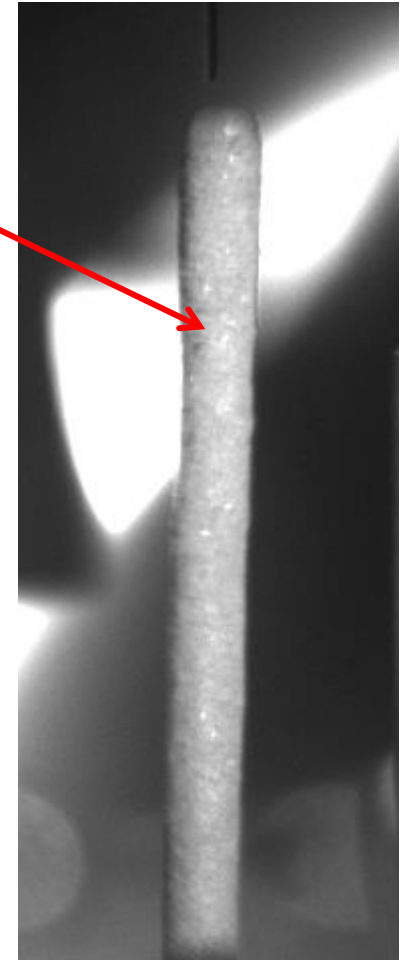
- 4H-SiC C-face ( $0-10^\circ$  off axis)
- $\sim 500 \mu\text{m} \times \sim 450 \mu\text{m}$

## Mounting

- Seed  $\sim 1.5$  cm long
- Ceramic pasted into an alumina tube
- After curing seed crystals cleaned
  - HCl:HNO<sub>3</sub> (2:1)
  - HF



2 mm dia.



# Source Material / Feed Rod

## Powders

- Fe(3N5), Si(2N), graphite (3N)
- -325 mesh or  $< 44 \mu\text{m}$  in dia.

## Feed Rod Processing

- Powders mixed by ball mill
- Formed into rods by cold isostatic press
- Sintered @  $1150^\circ\text{C}$ , 1 hour in hydrogen

# Growth Conditions

- 15 slm, Ultra High Purity Ar, @ ~115 Torr
- Pull rate: 100  $\mu\text{m}/\text{hour}$
- Feed rate: 10,000-1,000  $\mu\text{m}/\text{hour}$
- CO<sub>2</sub> laser ( $\lambda=10.6 \mu\text{m}$ ) @ 200-500 Watts
- Beam at heated zone :~4 mm wide x 2 mm high

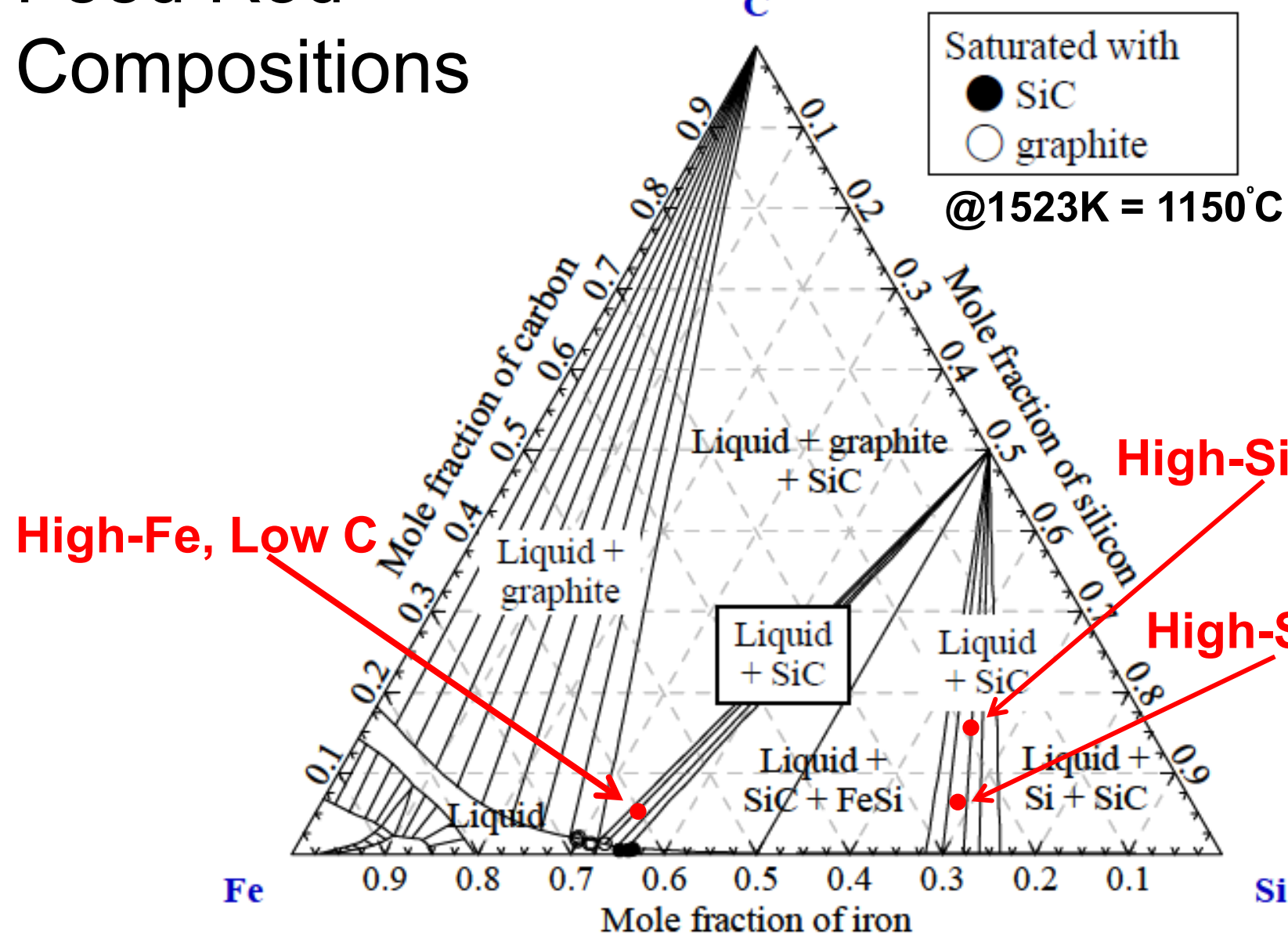
Note: Un-corrected temperature by optical pyrometer

Emissivity of the melt is unknown, ( $\epsilon_{\text{graphite}} = 0.9$ ,  $\epsilon_{\text{Fe}} = 0.2-0.4$ )<sup>1,2</sup>

<sup>1</sup> M.R. Null et al., J. Appl. Phys., 29, (1958) 1605

<sup>2</sup> H. B. Wahlin et al., Phys. Rev., 74, (1948) 687

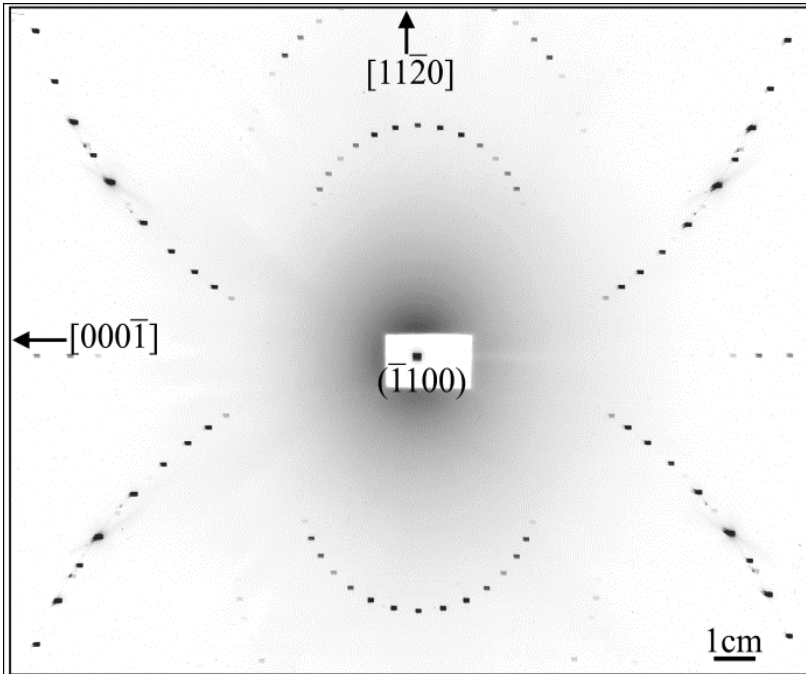
# Feed Rod Compositions



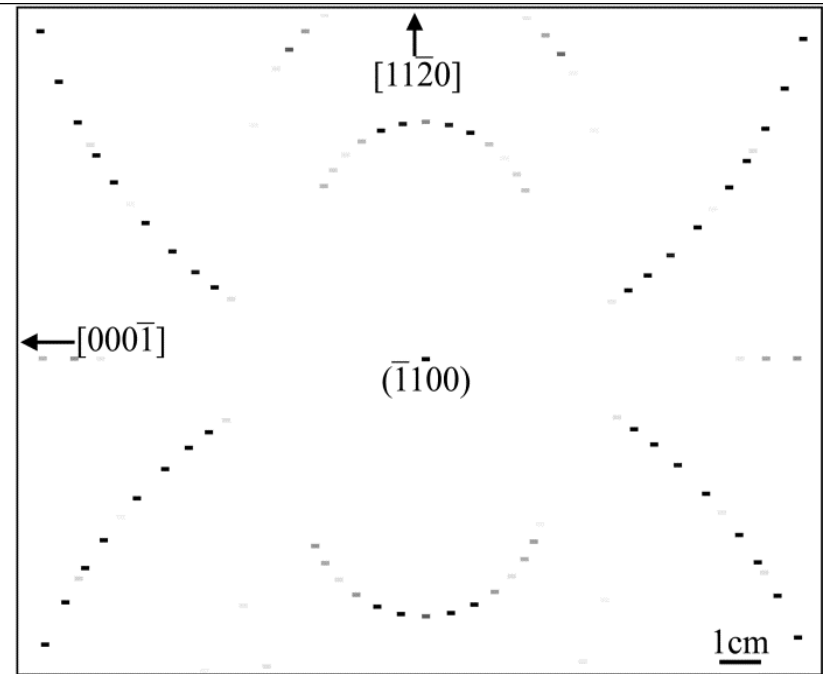
“Fundamental study for solvent growth of silicon carbide utilizing Fe-Si melt”, T Yoshikawa, S Kawanishi and T Tanaka, *International Conference on Advanced Structural and Functional Materials Design 2008*, Journal of Physics: Conference Series **165** (2009) 012022

# X-ray Transmission Laue Diffraction Pattern of Grown Crystals

Grown Crystal



Simulated\* 4H-SiC (1-100)

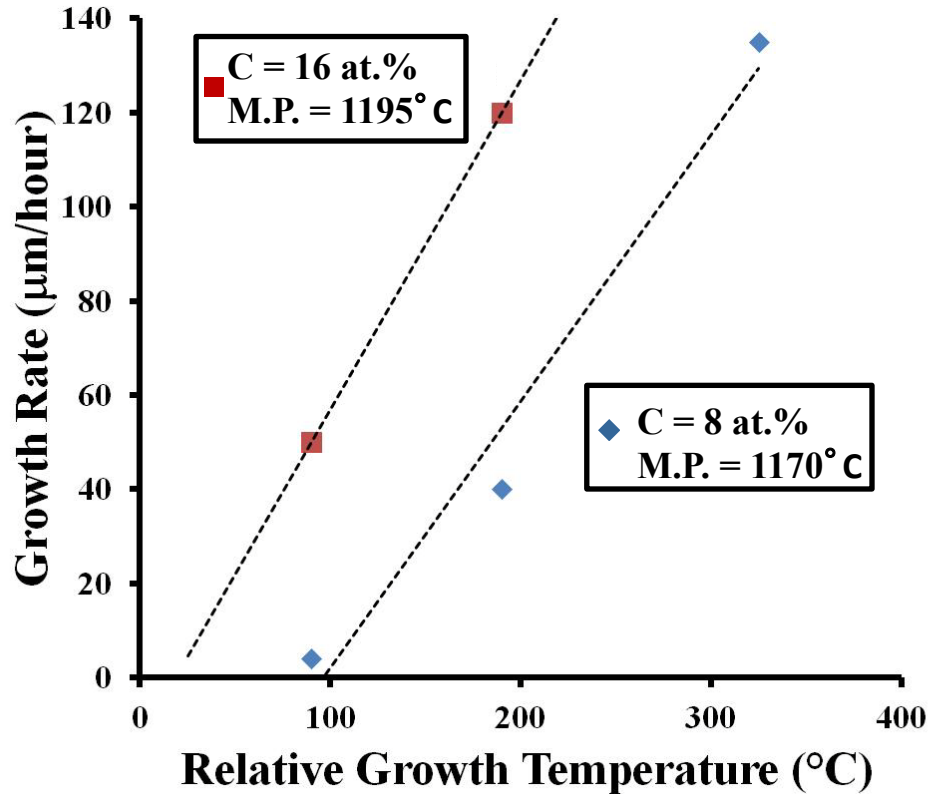


- Exact match between recorded and simulated patterns
- Grown crystals retain polytype and direction

- \*X. R. Huang, J. Appl. Cryst. (2010). 43, 926–928.
- Figure previously published: A.A. Woodworth, A. Sayir, P.G. Neudeck, B. Raghothamachar, M. Dudley, Characterization of 4H< 000-1> Silicon Carbide Films Grown by Solvent-Laser Heated Floating Zone, in: MRS Spring Symposium, San Francisco 2012



# Summary of Results



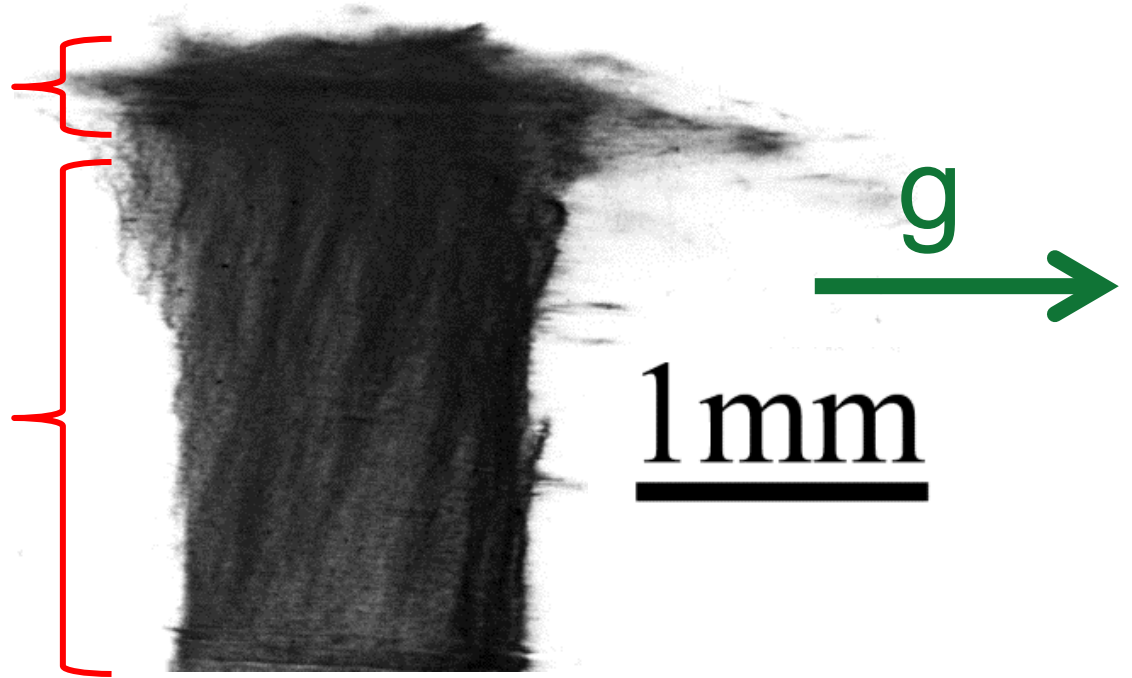
		Fe Concentration (atom/cm <sup>3</sup> )		
Fe/Si (atomic ratio)	C (at.%)	M.P. (°C)	M.P.+90 °C	M.P.+190 °C
High-Si (Fe/Si~0.35)	8	1170	~10 <sup>17</sup>	~10 <sup>17</sup>
	16	1195	~10 <sup>18</sup>	~10 <sup>18</sup>
High-Fe (Fe/Si~1.9)	8	N/A	No Growth	

- M.P.= temperature at which the feed rod formed a melt
- at.% =atomic percent
- Temperatures are not corrected for emissivity

# Synchrotron White Beam X-ray Topography

Grown Crystal Layer  
(High Distortion)

4H-SiC Seed

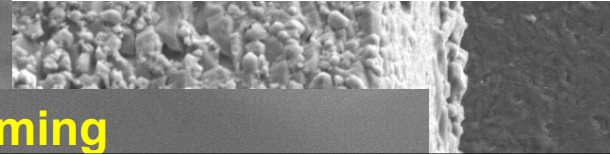
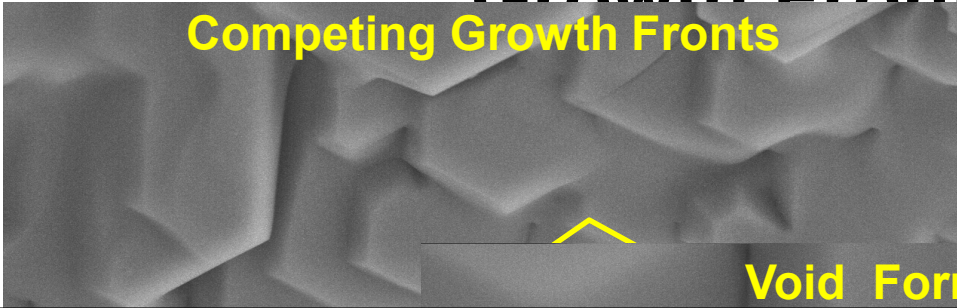


• Highly distorted X-ray topograph indicates significant inhomogeneous strain in the grown crystals

- Courtesy of Balaji Raghothamachar and Michael Dudley
- Image collected at Stony Brook Synchrotron Topography Station, Beamline X19C at the National Synchrotron Light Source, Brookhaven National Laboratory

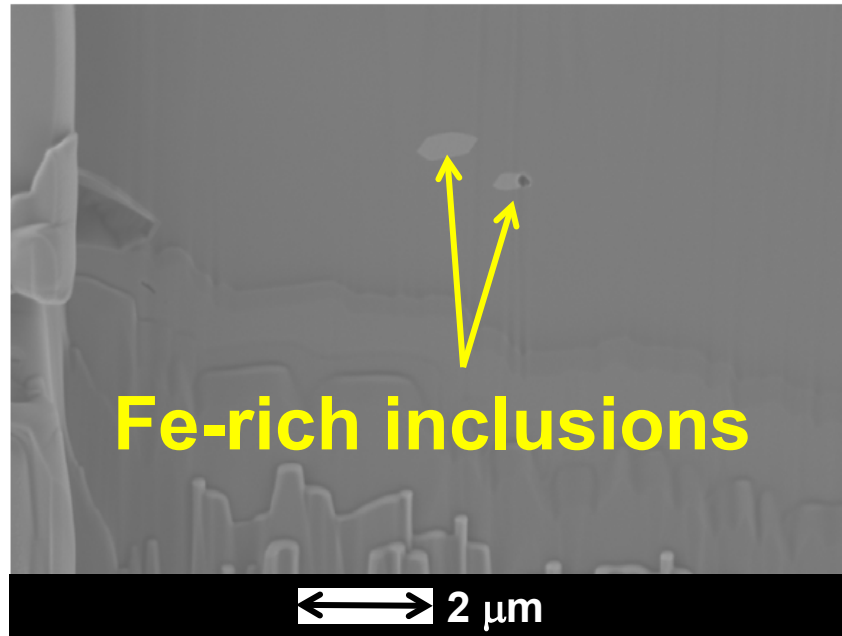
# Growth Front Evolution

Competing Growth Fronts

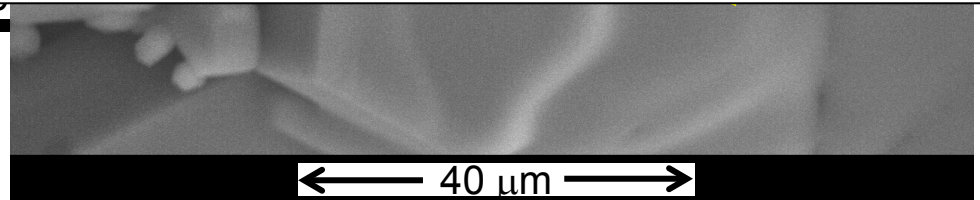


Void Forming

**FIB/EDS  
Cross Sectional  
Analysis**

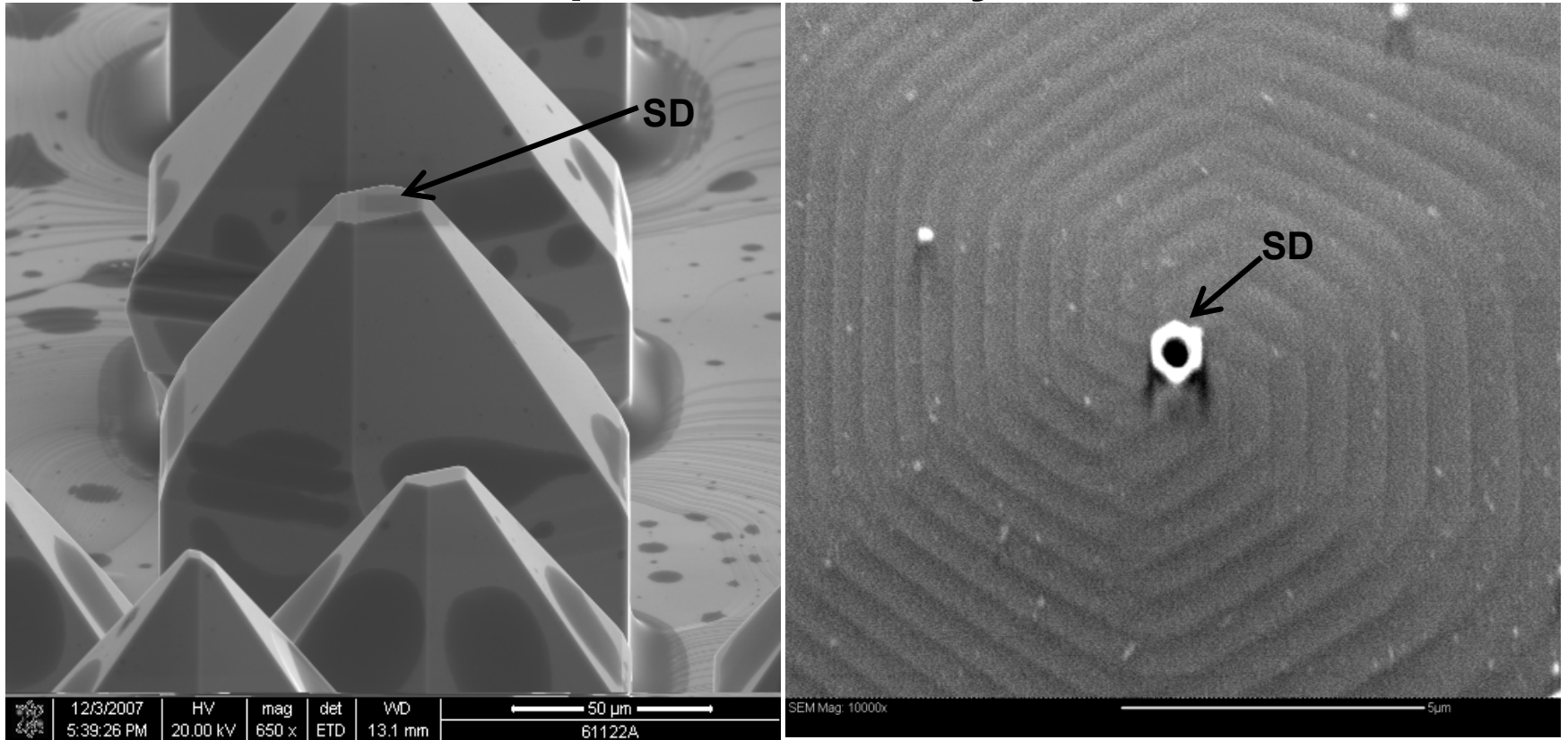


- Courtesy of Francisco Solá-López
- Figure previously published: A.A. Woodworth, A. Sayir, P.G. Neudeck, B. Raghoechamachar, M. Dudley, Characterization of 4H<000-1> Silicon Carbide Films Grown by Solvent-Laser Heated Floating Zone, in: MRS Spring Symposium, San Francisco 2012



# Growth Front Evolution (Cont.)

## Proposed Seed Crystal



Y. Picard *et al.*, MRS Symp. Proc. Vol. 1069, p. 151 (2008)



# Summary

- Initial studies show that Solvent-LHFZ readily grows SiC
- Growth rates increased with temperature and C present in the feed rod
- Fe incorporation increases with C present in the feed rod
- Grown crystal retained polytype but inclusions present create unwanted defects

# Future Work

- Implement seed single screw dislocation seed crystals
- Further refinement of source materials

# Team Members



## RHS

**(SiC growth, sensors & electronics)**

Phil Neudeck

Andy Trunek

David Spry

Michelle Mrdenovich-Hill (Sierra Lobo)

Beth Osborn (Sierra Lobo)

Chuck Blaha (Jacobs Technologies)

## RXC

**(Ceramics)**

Ali Sayir

Fred Dynys

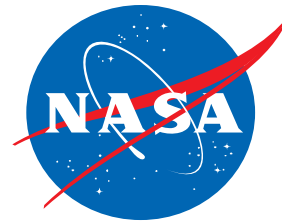
Thomas Sabo (CWRU/OAI)

## Special Thanks

Balaji Raghothamacher and Mike Dudley for Crystallography (Stony Brook SUNY) and Francisco Solá-López for FIB/EDS cross sectional analysis (NASA GRC)

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SiC Research at the NASA Glenn Research Center

<http://www.grc.nasa.gov/WWW/SiC/>